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* * * * * Welcome to STN International * * * * *

NEWS	1		Web Page for STN Seminar Schedule - N. America
NEWS	2	JUL 28	CA/CAPplus patent coverage enhanced
NEWS	3	JUL 28	EPFULL enhanced with additional legal status information from the epline Register
NEWS	4	JUL 28	IFICDB, IFIPAT, and IFIUDB reloaded with enhancements
NEWS	5	JUL 28	STN Viewer performance improved
NEWS	6	AUG 01	INPADOCDB and INPAFAMDB coverage enhanced
NEWS	7	AUG 13	CA/CAPplus enhanced with printed Chemical Abstracts page images from 1967-1998
NEWS	8	AUG 15	CAOLD to be discontinued on December 31, 2008
NEWS	9	AUG 15	CAPplus currency for Korean patents enhanced
NEWS	10	AUG 27	CAS definition of basic patents expanded to ensure comprehensive access to substance and sequence information
NEWS	11	SEP 18	Support for STN Express, Versions 6.01 and earlier, to be discontinued
NEWS	12	SEP 25	CA/CAPplus current-awareness alert options enhanced to accommodate supplemental CAS indexing of exemplified prophetic substances
NEWS	13	SEP 26	WPIDS, WPINDEX, and WPIX coverage of Chinese and Korean patents enhanced
NEWS	14	SEP 29	IFICLS enhanced with new super search field
NEWS	15	SEP 29	EMBASE and EMBAL enhanced with new search and display fields
NEWS	16	SEP 30	CAS patent coverage enhanced to include exemplified prophetic substances identified in new Japanese-language patents
NEWS	17	OCT 07	EPFULL enhanced with full implementation of EPC2000
NEWS	18	OCT 07	Multiple databases enhanced for more flexible patent number searching
NEWS	19	OCT 22	Current-awareness alert (SDI) setup and editing enhanced
NEWS	20	OCT 22	WPIDS, WPINDEX, and WPIX enhanced with Canadian PCT Applications
NEWS	21	OCT 24	CHEMLIST enhanced with intermediate list of pre-registered REACH substances
NEWS EXPRESS	JUNE 27 08		CURRENT WINDOWS VERSION IS V8.3, AND CURRENT DISCOVER FILE IS DATED 23 JUNE 2008.
NEWS HOURS			STN Operating Hours Plus Help Desk Availability
NEWS LOGIN			Welcome Banner and News Items
NEWS IPC8			For general information regarding STN implementation of IPC 8

Enter NEWS followed by the item number or name to see news on that specific topic.

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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 17:20:35 ON 19 NOV 2008

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=> file reg
COST IN U.S. DOLLARS          SINCE FILE      TOTAL
                               ENTRY      SESSION
FULL ESTIMATED COST          0.21        0.21
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FILE 'REGISTRY' ENTERED AT 17:21:07 ON 19 NOV 2008
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STRUCTURE FILE UPDATES: 18 NOV 2008 HIGHEST RN 1073232-10-6
DICTIONARY FILE UPDATES: 18 NOV 2008 HIGHEST RN 1073232-10-6

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH July 5, 2008.

Please note that search-term pricing does apply when conducting SmartSELECT searches.

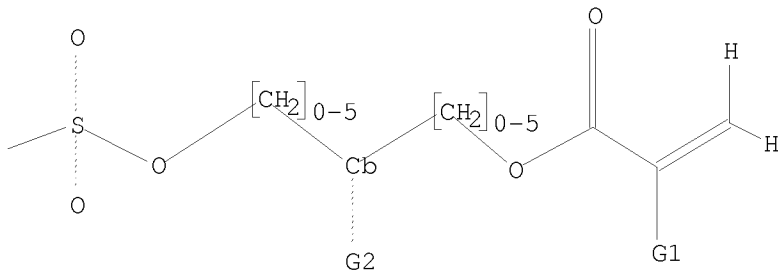
REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

<http://www.cas.org/support/stngen/stndoc/properties.html>

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Uploading C:\Program Files\Stnexp\Queries\10588080.str
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L1 STRUCTURE UPLOADED

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=> d l1
L1 HAS NO ANSWERS
L1 STR
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G1 H, Me, Et, CF3, CCl3, CBr3, CI3

G2 X, Ak, O

Structure attributes must be viewed using STN Express query preparation.

=> s l1

SAMPLE SEARCH INITIATED 17:21:33 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 1468 TO ITERATE

100.0% PROCESSED 1468 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 27062 TO 31658

PROJECTED ANSWERS: 0 TO 0

L2 0 SEA SSS SAM L1

=> s l1 full

FULL SEARCH INITIATED 17:21:37 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 29297 TO ITERATE

100.0% PROCESSED 29297 ITERATIONS

6 ANSWERS

SEARCH TIME: 00.00.01

L3 6 SEA SSS FUL L1

=> file caplus

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

178.36

178.57

FILE 'CAPLUS' ENTERED AT 17:21:42 ON 19 NOV 2008

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FILE COVERS 1907 - 19 Nov 2008 VOL 149 ISS 21

FILE LAST UPDATED: 18 Nov 2008 (20081118/ED)

Caplus now includes complete International Patent Classification (IPC) reclassification data for the third quarter of 2008.

Effective October 17, 2005, revised CAS Information Use Policies apply. They are available for your review at:

<http://www.cas.org/legal/infopolicy.html>

=> s l3

L4 4 L3

=> d l4 ibib abs hitstr 1-

YOU HAVE REQUESTED DATA FROM 4 ANSWERS - CONTINUE? Y/(N):y

L4 ANSWER 1 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2007:1237498 CAPLUS

DOCUMENT NUMBER: 147:494040

TITLE: Antireflective film coatings with good adhesion to far-UV, x-ray, or electron-beam resists and polymers therefor

INVENTOR(S): Okumura, Arimichi; Koyama, Hiroshi

PATENT ASSIGNEE(S): Daicel Chemical Industries, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 19pp.

CODEN: JKXXAF

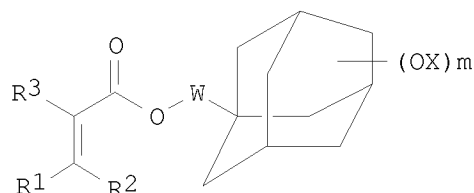
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2007284535	A	20071101	JP 2006-112392	20060414
PRIORITY APPLN. INFO.: GI			JP 2006-112392	20060414



I

AB The polymers are prepared from monomers I [R1-R3 = H, F, C1-6 (fluoro)alkyl; W = single bond, bridging group; m = 1, 2, 3; OX = OH, OSO2R4, OCOR5, OCOCH2COR6 (R4-R6 = alkyl; ≥1 of X is other than H)]. Coatings containing the polymers and their crosslinking agents, forming films effectively preventing upper resist patterns from degrading, are also claimed.

IT 952678-95-4P

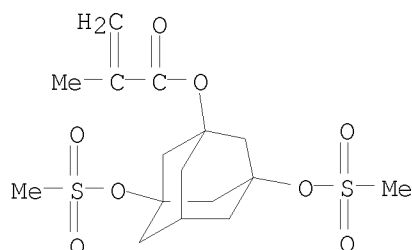
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(antireflective film coatings containing adamantane group-containing macromols.

and with good adhesion to radiation-sensitive photoresists)

RN 952678-95-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,5-bis[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



IT 953812-11-8P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(antireflective film coatings containing adamantane group-containing macromols.

and with good adhesion to radiation-sensitive photoresists)

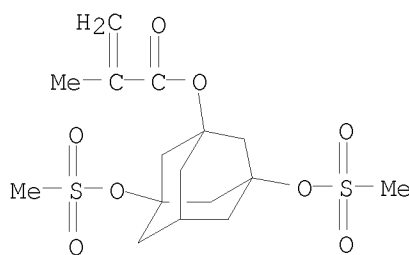
RN 953812-11-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,5-bis[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate and phenylmethyl 2-methyl-2-propenoate (CA INDEX NAME)

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CRN 952678-95-4

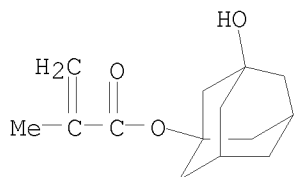
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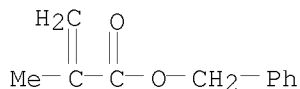
CMF C14 H20 O3



CM 3

CRN 2495-37-6

CMF C11 H12 O2



L4 ANSWER 2 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN

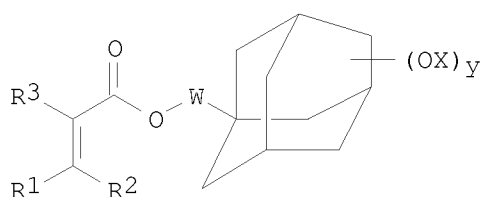
ACCESSION NUMBER: 2007:1237276 CAPLUS

DOCUMENT NUMBER: 147:511608

TITLE: Photoresist resin compositions with good substrate adhesion and dry etching resistance, their (meth)acryl monomers, and their macromolecules

INVENTOR(S): Koyama, Hiroshi; Murai, Yoshiyuki; Nishimura, Masamichi
 PATENT ASSIGNEE(S): Daicel Chemical Industries, Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 25pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2007284381	A	20071101	JP 2006-114129	20060418
PRIORITY APPLN. INFO.:			JP 2006-114129	20060418
OTHER SOURCE(S):	MARPAT 147:511608			
GI				



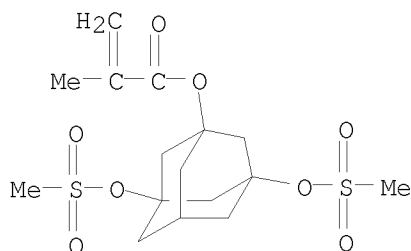
I

AB Monomers represented by I [R1-R3 = H, F, C1-6 (fluoro)alkyl; W = single bond, bridging group; y = 1-3; OX = OSO2Rd, OCORe, OCOCH2CORf (Rd, Re, Rf = alkyl)], their polymers preferably having acid-labile alkali-soluble groups, and photoresist compns. containing the macromols. and photoacid generators are sep. claimed. Also claimed is a process for applying the photoresists on substrates, exposing, and developing to form precision patterns.

IT 952678-95-4P
 RL: IMF (Industrial manufacture); RCT (Reactant); TEM (Technical or engineered material use); PREP (Preparation); RACT (Reactant or reagent); USES (Uses)
 (pos. photoresists containing acid-labile macromols. having good balance between dry etching resistance, solvent solubility, and alkali developability)

RN 952678-95-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,5-bis[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



IT 955027-97-1P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(pos. photoresists containing acid-labile macromols. having good balance between dry etching resistance, solvent solubility, and alkali developability)

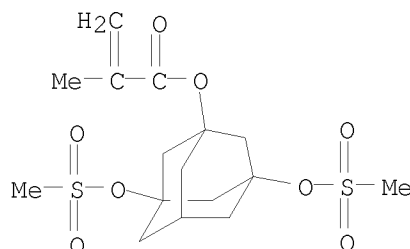
RN 955027-97-1 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,5-bis[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-methyl-2-propenoate and 1-methyl-1-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl 2-methyl-2-propenoate (CA INDEX NAME)

CM 1

CRN 952678-95-4

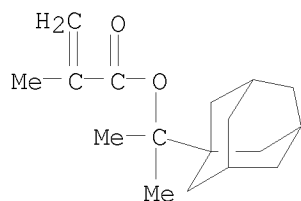
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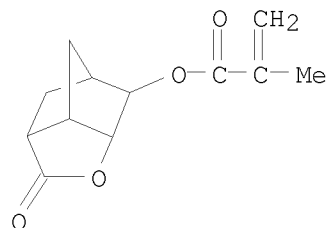
CMF C17 H26 O2



CM 3

CRN 254900-07-7

CMF C12 H14 O4



DOCUMENT NUMBER: 147:477561
 TITLE: Substituted adamantyl (meth)acrylate monomers,
 photoresist protective films of their polymers for
 semiconductors in immersion exposure, and manufacture
 of semiconductors using them
 INVENTOR(S): Koyama, Hiroshi; Okumura, Arimichi
 PATENT ASSIGNEE(S): Daicel Chemical Industries, Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 17pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2007284368	A	20071101	JP 2006-111911	20060414
PRIORITY APPLN. INFO.:			JP 2006-111911	20060414
OTHER SOURCE(S):	MARPAT 147:477561			

AB The invention relates to (meth)acrylate monomers of C(R1)(R2):C(R3)CO2WQ1
 [R1 - R3 = H, F, (H or F-substituted) C1-6 alkyl; W = single bond, linking
 group; Q1 = (XO)m-substituted 5-adamantyl; m = 1-3; OX = OSO2R4, O2CR5,
 O2CCH2COR6; R4 - R6 = (substituted)alkyl]. Pos. photoresists patterned by
 immersion exposure using the substituted adamantyl (meth)acrylate polymer
 films showed high fineness and accuracy.

IT 952678-98-7P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (protective film; substituted adamantyl (meth)acrylate polymer
 protective films for semiconductor photoresists by immersion exposure)

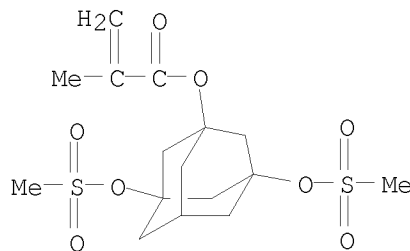
RN 952678-98-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with
 3,5-bis[(methylsulfonyl)oxy]tricyclo[3.3.1.1.3,7]dec-1-yl
 2-methyl-2-propenoate and cyclohexyl 2-methyl-2-propenoate (CA INDEX
 NAME)

CM 1

CRN 952678-95-4

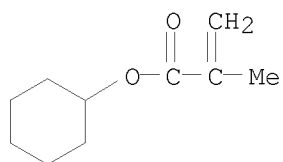
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CRN 101-43-9

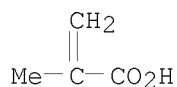
CMF C10 H16 O2



CM 3

CRN 79-41-4

CMF C4 H6 O2



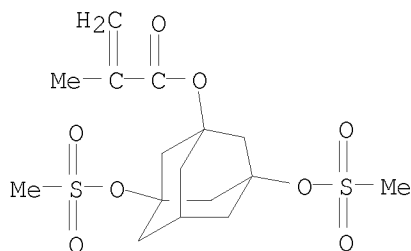
IT 952678-95-4P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(substituted adamantyl (meth)acrylate polymer protective films for semiconductor photoresists by immersion exposure)

RN 952678-95-4 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,5-bis[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-1-yl ester (CA INDEX NAME)



L4 ANSWER 4 OF 4 CAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2006:386486 CAPLUS

DOCUMENT NUMBER: 144:422706

TITLE: Acrylic acid ester-based polymers, positive resist compositions, and formation of resist patterns

INVENTOR(S): Ogata, Toshiyuki; Matsumaru, Shogo; Shiono, Hirotooshi; Haneda, Hideo

PATENT ASSIGNEE(S): Tokyo Ohka Kogyo Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 54 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

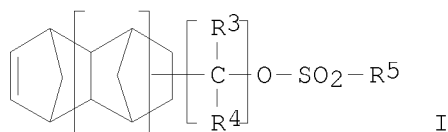
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2006111733	A	20060427	JP 2004-300716	20041014
PRIORITY APPLN. INFO.:			JP 2004-300716	20041014
OTHER SOURCE(S):		MARPAT 144:422706		

GI



AB The polymers are (A) α -lower alkyl acrylate-based units having acid-dissociating and dissoln.-inhibiting groups and (B) $\text{CH}_2\text{CR}[\text{C}(\text{:O})\text{O}(\text{CR}_1\text{R}_2)\text{sX}((\text{CR}_3\text{R}_4)\text{tOSO}_2\text{R}_5)]\text{u}$ [R, R1-R4 = H, lower alkyl; R1 = R2 \neq alkyl; R5 = (halogenated) lower alkyl; s, t = 0-3; u = 1-3; X = cyclic group]. The resist compns. comprise the polymers, whose alkali solubility is increased by the action of acids, and acid generators. Resist patterns are formed by applying the compns. on substrates, exposing, and developing. Sulfonic acid group-containing norbornene derivs. I [R3, R4 = H, lower alkyl; R5 = (halogenated) lower alkyl; a = 0, 1; t = 0-3] are also claimed. Resolution of the resist compns. is improved.

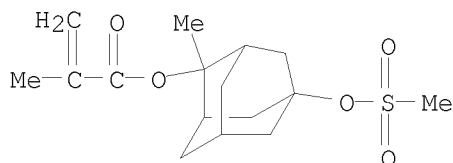
IT 883868-04-0P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (sulfonyl-containing acrylate-based polymers for high-resolution pos. resist compns.)

RN 883868-04-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 2-methyl-5-[(methylsulfonyl)oxy]tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

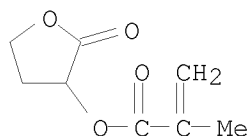
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CM 2

CRN 195000-66-9
 CMF C8 H10 O4



CM 3

CRN 115372-36-6
CMF C14 H20 O3

